REMARKS

This is in response to the Office Action dated December 14, 2004.

Applicant respectfully submits that claims 1, 10, and 11 as amended, as well as newly added independent claim 30, are in condition for allowance.

Examiner rejects claims 1-28 based solely on Yoon et al, U.S. 6,800,418. Applicant's claim 1 includes the limitation of, "a **negative tone photoresist** having at least **a cycloolefin functionalized with a di-ol**." Applicant's specification, at page 2 in paragraph 0005, states, "A negative tone photoresist become less solulable to a developer solution upon exposure to light." Therefore, upon exposing the photoresist to light, the exposed portions become less solulable as compared to the non-exposed portions.

However, Yoon et. al does not teach, disclose, or suggest the use of a negative tone photoresist. In fact, formula 2 in col. 2, illustrates a positive tone photoresist, where the resist composition becomes more solulable upon exposure to radiation. Furthermore, Yoon et. al is targeted to, "provide a photosensitive polymer having a structure to give a high transmittance at a F₂ excimer laser wavelength of 157nm and good adhesion to an underlying layer," not a negative tone photoresist composition. In formula 4 in col. 3, Yoon et al discloses repeating units that do not react after exposure to radiation, rather provide the good transmittance, hydrophilicity, and adhesion.

Applicant's claim 11 includes the limitation of "depositing a negative tone photoresist." Moreover, applicant's newly added independent claim 30, includes a similar limitation, wherein upon exposure to radiation/light the photoresist becomes less solulable to a developer solution, i.e. a negative tone photoresist. Therefore, for the same reasons as state above in reference to claim 1, applicant submits that claims 11 and 30 are not anticipated by Yoon et. al.

Applicant's claim 10 illustrates a negative tone photoresist. Yoon et. al does not disclose a negative tone photoresist, let alone the specific chemical structure illustrated in claim 10.

Therefore, since claims 2-9, 12-29, and 31-32 depend from claims 1, 11, and 30, applicant respectfully submits that they are also in condition for allowance for at least the same reasons stated above.

If there are any additional charges, please charge Deposit Account No. 02-2666. If a telephone interview would in any way expedite the prosecution of the present application, the Examiner is invited to contact Edwin H. Taylor at (408) 720-8300.

Respectfully submitted,

BLAKELY, SOKOLOFF, TAYLOR & ZAFMAN LLP

Dated: $V/_{2}C$, 2005

Edwin H. Taylor Reg. No. 25,129

12400 Wilshire Blvd. Seventh Floor Los Angeles, CA 90025-1026 (408) 720-8300